

REMARKS

Applicant requests favorable reconsideration and allowance of the subject application in view of the preceding amendments and the following remarks.

To place the subject application in better form, the specification has been amended to correct minor informalities. Also, a new abstract is presented in accordance with preferred practice. No new matter has been added by these changes.

In the above-noted Office Action, the Examiner stated that the PTO-1449 form submitted with the Supplemental Information Disclosure Statement filed on November 20, 2003, contained an informality. To correct this, Applicant filed a Letter Submitting Corrected PTO-1449 Form, on June 6, 2005. Applicant requests that the Examiner consider the material cited in the Supplemental Information Disclosure Statement filed on November 20, 2003, and initial and return a copy of the corrected PTO-1449 form submitted on June 6, 2005, indicating his consideration of the cited document.

Claims 11-16 are presented for consideration in lieu of claims 1-10, which have been canceled without prejudice or disclaimer. Claim 11 is the sole independent claim. Support for these claims can be found in the original application, as filed. Therefore, no new matter has been added.

Applicant requests favorable reconsideration and withdrawal of the rejections set forth in the above-noted Office Action.

Claims 1, 3-7, 9 and 10 were rejected under 35 U.S.C. § 103(a) as being unpatentable over U.S. patent application publication number 2002/0055102 to Emoto in view of U.S. Patent

No. 6,765,647 to Nishi. Claims 2 and 8 were rejected under 35 U.S.C. § 103(a) as being unpatentable over the Emoto publication in view of the Nishi patent as applied to claim 1 above, and further in view of U.S. Patent No. 6,437,851 to Hagiwara. Applicant submits that the cited art, whether taken individually or in combination, does not teach or suggest many features of the present invention, as previously recited in claims 1-10. Therefore, this rejection is respectfully traversed. Nevertheless, Applicant submits that claims 11-16, as presented, amplify the distinctions between the present invention and the cited art.

Independent claim 11 recites an exposure apparatus for exposing a substrate to a pattern of a reticle. The apparatus includes a stage to hold one of the substrate and the reticle, a motor to drive said stage, the motor including a coil and a jacket to cover the coil, and a first adjustment system to adjust temperature of said motor. The first adjustment system includes a flow path of pure water through the jacket, and an impurity removing unit, arranged upstream with respect to the jacket in the flow path, to remove an impurity in the pure water.

Applicant submits that the cited art does not teach or suggest such features of the present invention, as recited in independent claim 11.

The Examiner relies on the Emoto document for disclosing a device manufacturing apparatus that has a plurality of objects to be temperature-adjusted and including a plurality of temperature adjustment systems which respectively temperature-adjust the plurality of objects to be temperature-adjusted. The Examiner considers the plurality of temperature adjustment systems to include a first temperature adjustment system that uses any one coolant selected from the group consisting of pure water, a fluorine-based inert solution, a gas, and antifreeze, and a

second temperature adjustment system that uses any one coolant selected from that grouping.

The Examiner further considers the Emoto document to teach a first temperature system constituted by a closed path, with the first and second temperature adjustment systems arranged to operate independently.

The Examiner relies on the Nishi patent for teaching a temperature adjustment unit that uses a fluorine based inert solution to control temperature of the wafer and a projection system.

Further, the Examiner relies on the Hagiwara patent for disclosing a temperature adjustment system for air that circulates through an exposure section and an impurity removing unit.

Applicant submits, however, that none of the citations, whether taken individually or in combination, teaches or suggests salient features of the exposure apparatus of the present invention recited in independent claim 11, including the arrangement of the stage, the motor and the first adjustment system. Specifically, Applicant submits that the cited art does not teach or suggest at least the first adjustment system which is provided to adjust temperature of the motor, the first adjustment system having a flow path of pure water through the jacket of the motor, and an impurity removing unit, arranged upstream with respect to the jacket in the flow path, to remove an impurity in the pure water. Accordingly, that art does not teach or suggest many features of Applicant's present invention, as recited in independent claim 11.


For the foregoing reasons, Applicant submits that the present invention, as recited in independent claim 11, is patentably defined over the cited art, whether that art is taken individually or in combination.

Dependent claims 12-16 also should be deemed allowable, in their own right, for defining other patentable features of the present invention in addition to those recited in independent claim 11. Further individual consideration of these dependent claims is requested.

Applicant further submits that the instant application is in condition for allowance. Favorable reconsideration, withdrawal of the rejections set forth in the above-noted Office Action and an early Notice of Allowance are requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our address given below.

Respectfully submitted,



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